

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	92	(photoresist or resist or photo-resist or photo near resist) with (inorganic near3 salt)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:33
L2	6	(photoresist or resist or photo-resist or photo near resist) with (inorganic near3 salt) and (precursor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:16
L3	5	2 and (film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:16
L4	0	(photoresist or resist or photo-resist or photo near resist) with (in-organic near3 salt)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:20
L5	103	(photoresist or resist or photo-resist or photo near resist) with (inorganic near5 salt)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:21
L6	2	(photoresist or resist or photo-resist or photo near resist) with (dissolv\$3) with (inorganic near5 salt)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:22
L7	5324	(photoresist or resist or photo-resist or photo near resist) and (inorganic near5 salt)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:22
L8	30	(photoresist or resist or photo-resist or photo near resist) and (inorganic near5 salt) and (precursor) and (ceramic near3 film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:25
L9	4	8 and (inorganic) with (photoresist or resist or photo-resist or photo near resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:25

L10	59	(photoresist or resist or photo-resist or photo near resist) and (inorganic near5 salt) and (liquid or solution) and (ceramic near3 film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:24
L11	4	10 and (inorganic) with (photoresist or resist or photo-resist or photo near resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:25
L12	5	(photoresist or resist or photo-resist or photo near resist) and (inorganic near5 salt) and (precursor) and (ceramic near film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:29
L13	35	(photoresist or resist or photo-resist or photo near resist) and (metal near3 alkoxides) and (precursor) and (ceramic near film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:30
L14	0	13 and dissov\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:30
L15	34	13 and dissolv\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:30
L16	1	15 and (photoresist or resist or photo-resist or photo near resist) with (dissolv\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:31
L17	4942	(photoresist or resist or photo-resist or photo near resist) with (inorganic or metal near alkoxides)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:34
L18	542	(photoresist or resist or photo-resist or photo near resist) with (inorganic or metal near alkoxides) and (precursor) and (film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:34
L19	3	(photoresist or resist or photo-resist or photo near resist) with (soluble) near5 (inorganic or metal near alkoxides) and (precursor) and (film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:36

L20	2	(photoresist or resist or photo-resist or photo near resist) with ((soluble) near5 (inorganic or metal near alkoxides) )	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:37
L21	37	(photoresist or resist or photo-resist or photo near resist) with ((soluble) near5 (inorganic or metal near alkoxides) )	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:41
L22	37	(photoresist or resist or photo-resist or photo near resist) with ((soluble) near5 (inorganic or metal near3 alkoxides) )	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:44
L23	1469	(photoresist or resist or photo-resist or photo near resist or metal near salts) with ((soluble) near5 (inorganic or metal near3 alkoxides) )	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:44
L24	1469	((photoresist or resist or photo-resist or photo near resist) or (metal near salts)) with ((soluble) near5 (inorganic or metal near3 alkoxides) )	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:10
L25	40	24 and (precursor) with (film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:45
L26	2	24 and (precursor) with (ceramic near3 film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:08
L27	0	24 and (liquid near3 solution) with (ceramic near3 film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:49
L28	3	24 and (liquid or aqueous or solution) with (ceramic near3 film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:50
L29	2354	((photoresist or resist or photo-resist or photo near resist) or (metal near5 salts)) with ((soluble) near5 (inorganic or metal near3 alkoxides) )	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:53

L30	36538	((photoresist or resist or photo-resist or photo near resist) or (metal near3 salts)) with ((inorganic or metal near3 alkoxides) )	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:53
L31	8	30 and (precursor) with (ceramic near film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:59
L32	0	30 and (liquid near3 solution) with (ceramic near film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 14:59
L33	7	30 and (liquid or solution) with (ceramic near film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:03
L34	19	30 and (solution) with (ceramic near3 film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:04
L35	11	34 and precursor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:04
L36	11	35 and (solution) near25 (ceramic)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:04
L37	10	35 and (solution) near15 (ceramic)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:04
L38	5	35 and (solution) near15 (ceramic near film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:04
L39	2	24 and (precursor) with (ceramic near5 film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:09

L40	2	24 and (precursor) with (ceramic\$1 near5 film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:09
L41	20	24 and (precursor) with (ceramic\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:10
L42	16	24 and (precursor) near10 (ceramic\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:10
L43	1304	((photoresist or resist or photo-resist or photo near resist) or (metal near salts)) near15 ((soluble) near5 (inorganic or metal near3 alkoxides) )	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:10
L44	15	43 and (precursor) near10 (ceramic\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:12
L45	2	43 and (precursor) with (ceramic\$1 near film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/10 15:12